

What is claimed is:

1        1. A cleaning device comprising:  
2            a pure water supply;  
3            first and second injectors that eject pure water supplied from the pure water supply onto a  
4            wafer;  
5            first and second nozzles attached to ends of the respective first and second injectors;  
6            a brush that cleans the wafer during horizontal movement between a center and edges of  
7            the wafer; and  
8            a brush arm that supports and moves the brush,  
9            wherein the first injector ejects the pure water at an upper position of the wafer toward  
10          the center of the wafer, and  
11          wherein the second injector is disposed adjacent to the brush along one side of the brush  
12          arm, and supplies the pure water toward the wafer.

1        2. The cleaning device as recited in claim 1, wherein the second nozzle is disposed such  
2          that it faces a top surface of the wafer that is in contact with the brush.

1        3. The cleaning device as recited in claim 1, wherein the first injector is arranged to be  
2          perpendicular to the second injector.

1        4. The cleaning device as recited in claim 3, wherein the brush arm moves in a direction  
2          parallel to linear orientation of the first injector.

5. The cleaning device as recited in claim 1, wherein the brush arm is moved vertically to keep the brush a desired distance from a surface of the wafer.

6. The cleaning device as recited in claim 1, wherein the brush arm is moved vertically to keep the brush in contact with a surface of the wafer.

7. The cleaning device as recited in claim 1, wherein the brush moves horizontally with respect to the direction of the first injector.

8. A cleaning device comprising:
  - a pure water supply;
  - first injector that ejects pure water supplied from the pure water supply onto a central portion of the wafer;
  - a plurality of second injectors that eject pure water supplied from the pure water supply onto the wafer;
  - a first nozzle attached to the first injector;
  - a plurality of second nozzles respectively attached to the second injectors;
  - a brush that cleans the wafer during horizontal movement between a center and edges of the wafer, while the pure water is ejected by the first and second nozzles; and
  - a brush arm that supports and moves the brush,

13 circumference of the brush arm, the end of the pipelines facing a top surface of the wafer.

1 9. The cleaning device as recited in claim 8, wherein the plurality of second injectors are  
2 tightly fixed to the brush arm by a fixing apparatus.

1 10. The cleaning device as recited in claim 8, wherein the first injector is arranged to be  
2 perpendicular to the plurality of second injectors.

1 11. The cleaning device as recited in claim 10, wherein the brush arm moves in a  
2 direction parallel to a linear orientation of the first injector.

1 12. The cleaning device as recited in claim 8, wherein the brush arm is moved vertically  
2 to keep the brush a desired distance from a surface of the wafer.

1 13. The cleaning device as recited in claim 8, wherein the brush arm is moved vertically  
2 to keep the brush in contact with a surface of the wafer.